

Poster Session 3

March 7 (Wed), 13:00-14:30

- P3001A **Preparation of functional thin films using powder target by sputtering deposition method**
 H. Kawasaki, K. Arafune, T. Ohshima, Y. Yagyu, Y. Suda
 Sasebo National College of Technology, Japan
- P3002A **Electrical properties of ZnO-doped Nd(Co_{1/2}Ti_{1/2})O₃ thin films by RF magnetron sputtering**
 C. Hsu, Y. He
 National United University, Taiwan
- P3003A **Si thin film humidity sensors prepared by hot wire CVD at various hydrogen gas flow rates**
¹Y. Chen, ²T. Hsueh, ¹C. Hsu
¹National University of Tainan, Taiwan
²National Nano Device Laboratories, Taiwan
- P3005A **Dependence on nitrogen gas pressure of a-CN_x thin films prepared by reactive sputtering**
 C. Iwasaki, M. Aono, N. Tamura, N. Kitazawa, Y. Watanabe
 National Defense Academy, Japan
- P3006A **A study on the very low room-temperature electrical resistivity of Ti_xFeCoNiO_y oxide thin films**
¹Y. Yang, ²L. Wu, ²C. Tsau, ¹J. Yeh
¹National Tsing Hua University, Taiwan
²Chinese Culture University, Taiwan
- P3007A **Observation of surface gas depletion in the tube during internal DLC coating with microwaves**
 R. Matsui, H. Kousaka, N. Umehara
 Nagoya University, Japan
- P3008A **The effect of Cu thickness on the AZO/Cu/AZO tri-layer transparent conducting film**
 Y. Lin, Y. Huang, Y. Lin, Y. Wang, C. Cai
 I-Shou University, Taiwan
- P3009A **The enhanced antireflection on silicon base solar cell by sputtering SiO₂/TiO₂ double thin films**
¹Y. Lin, ¹C. Lin, ¹I. Yang, ¹W. Lo, ¹W. Lin, ²C. Chen
¹I-Shou University, Taiwan
²Cheng Shiu University, Taiwan

- P3010A **The effect of Al thickness on the Al/AZO double-layer transparent conducting film**
Y. Lin, Y. Lin, Y. Wang, Y. huang, C. Cai
I-Shou University, Taiwan
- P3011A **The enhanced antireflection on silicon base solar cell by sputtering SiO₂ or TiO₂ single thin films**
Y. Lin, I. Yang, W. Lo, C. Lin, W. Lin
I-Shou University, Taiwan
- P3012A **A comparison of DLC film properties obtained by PECVDs with DC plasma and microwave-excited high-density plasma**
Y. Takaoka, H. Kousaka, N. Umehara
Nagoya University, Japan
- P3013A **Deposition of DLC films by high power pulsed sputtering magnetron discharges**
T. Kimura, R. Nishimura
Nagoya Institute of Technology, Japan
- P3014A **Application of TiN/TiO₂ films for anti-fog and anti-freeze mirror**
S. Sharma, A. Pandey, S. Ikezawa
Chubu University, Japan
- P3015A **Apatite-type lanthanum silicate films prepared by atmospheric-pressure plasma jet**
Y. SU, Y. Kuo
National Taiwan University of Science and Technology, Taiwan
- P3016A **Effect of hydrogen dilution on ZnO thin films fabricated via nitrogen mediated crystallization**
I. Suhariadi, K. Matsushima, K. Kuwahara, K. Oshikawa, K. Nakahara, D. Yamashita, H. Seo, G. Uchida, K. Kamataki, K. Koga, M. Shiratani, N. Itagaki
Kyushu University, Japan
- P3017A **Interaction between amplitude modulated plasma and nanoparticle growth in the plasmas**
¹K. Kamataki, ²K. Koga, ³G. Uchida, ^{2,3}N. Itagaki, ²H. Seo, ²M. Shiratani
¹Kyushu University, Japan
²Kyushu University, Japan
³Japan Science and Technology Agency, Japan

- P3018A **Crystallographic analysis of amorphous carbon films synthesized by radical-injection plasma-enhanced chemical vapor deposition**
L. Yu, J. Kuki, H. Kondo, K. Ishikawa, M. Sekine, M. Hori
Nagoya University, Japan
- P3019A **Formation of indium-zinc-oxide film using RF magnetron sputtering diagnosed by ultra violet absorption spectroscopy**
¹M. Inoue, ²T. Ohta, ¹N. Takota, ²M. Ito, ³M. Hori
¹Wakayama University, Japan
²Meijo University, Japan
³Nagoya University, Japan
- P3020A **Enhancement of ITO layer adhesion to PET film treated by microwave plasma in roll coater**
¹H. Ogawa, ¹K. Kato, ¹K. Nakamura, ²K. Iseki, ¹H. Sugai
¹Chubu University, Japan
²Toyobo Co., Ltd., Japan
- P3021A **Effect of hydrogen radical injection on plasma enhanced chemical vapor film deposition of microcrystalline silicon**
¹Y. Lu, ¹A. Fukushima, ¹Y. Abe, ¹K. Takeda, ¹K. Ishikawa, ¹H. Kondo, ^{1,2}M. Sekine, ^{1,2}M. Hori
¹Nagoya University, Japan
²JST-CREST, Japan
- P3023A **Microwave plasma source for CVD diamond devices fabrication**
¹B. Paosawatyanyong, ^{1,2}N. Rujisamphan, ¹W. Bhanthumnavin
¹Chulalongkorn University, Thailand
²ThEP Center, Commission on Higher Education, Thailand
- P3024A **Automated langmuir probe system for CVD deposition process**
D. Lapsongphol, S. Thitianan, W. Bhanthumnavin, B. Paosawatyanyong
Chulalongkorn University, Thailand
- P3025A **Development of internal DLC coating method without surface roughness**
A. Hanihara, H. Kousaka, T. Tokoroyama, N. Umehara
Nagoya University, Japan
- P3026A **Effects of RF bias on optical properties of amorphous carbon films grown by plasma-enhanced chemical vapor deposition**
¹J. Kuki, ¹L. Yu, ²H. Kondo, ²K. Ishikawa, ^{1,2}M. Sekine, ^{1,2}M. Hori
¹Nagoya University, Japan
²Nagoya University, Japan

P3027A	Adhesion effect of TiO₂ film on glass
	S. Ikezawa	
	Chubu University, Japan	
P3028A	Effect of oxygen addition in AZO DC sputtering
	¹ N. Shih, ² C. Lin, ² C. Kung	
	¹ Hsiuping University of Science and Technology, Taiwan	
	² National Chung-Hsing University, Taiwan	
P3029A	Effect of non-lattice oxygen on Cu_xO-based resistive switching memory
	C. Lin, P. Wu, Y. Chang	
	National Dong Hwa University, Taiwan	
P3030A	Effect of DC-power for Ti-target on the composition, structure and characterization of the Ti (0-2.36at.%), Al-co-doped ZnO sputtering thin films
	J. Lin	
	Central University, Taiwan	
P3031A	Deposition of highly insulating nitrides (AlN and BN) by HiPIMS technique : Correlation between time resolved investigations and physical properties of AlN and BN films
	A. Djouadi	
	Institut des matériaux Jean Rouxel, France	
P3032A	Phosphor efficiency of Mn-doped Zn₂SiO₄ thin films enhanced by nano-silver surface plasmon
	¹ C. Peng, ¹ K. Hsieh, ² S. Liu, ¹ Y. Lin, ³ C. Tseng, ³ J. Lin	
	¹ Mingchi University of Technology, Taiwan	
	² National Taiwan Normal University, Taiwan	
	³ National Central University, Taiwan	
P3033A	Amorphous CN_x coatings deposited by CVD-PVD hybrid technique
	¹ T. Takeno, ² M. Aono, ¹ T. Takagi	
	¹ Tohoku University, Japan	
	² National Defense Academy, Japan	

- P3034A **Structure and characterization of aluminum doped Zn₂SiO₄ thin film prepared by magnetron sputtering**
¹K. Peng, ²L. Jing-chie, ³L. Shiu-jen, ¹H. Keng-lin, ¹L. Yi-tsung, ²T. C.A.
¹Mingchi University of Technology, Taiwan
²National Central University, Taiwan
³National Taiwan Normal University, Taiwan
- P3035A **Etching rate of carbon films deposited by H-assisted plasma CVD**
¹T. Urakawa, ¹R. Torigoe, ¹H. Seo, ¹G. Uchida, ^{1,2}N. Itagaki, ^{1,3}K. Koga, ^{1,3}M. Shiratani, ^{3,4}Y. Setsuhara, ^{3,5}M. Sekine, ^{3,5}M. Hori
¹Kyushu University, Japan
²PRESTO, Japan
³CREST, Japan
⁴Osaka University, Japan
⁵Nagoya University, Japan
- P3037A **Low temperature growth of ZnO using atmospheric pressure N₂ / O₂ plasma**
¹Y. Nose, ²T. Uehara, ¹N. Fujimura
¹Osaka Prefecture University, Japan
²Sekisui Chemical Co., Ltd., Japan
- P3038A **Optical emission characteristics of Nanoparticle-supressed plasma CVD for microcrystalline silicon films deposition**
Y. Kim, T. Matsunaga, H. Seo, G. Uchida, K. Kamataki, N. Itagaki, K. Koga, M. Shiratani
Kyushu University, Japan
- P3039A **TCO-less dye-sensitized solar cells used molybdenum thin film as a charge collector**
¹D. Kim
¹Sungkyunkwan University, Korea
²Interdisciplinary Graduate School Program for Photovoltaic Specialists (IPPs), Korea
- P3041A **Intermediate band formation of ZnTe layer by oxyge incorporation**
S. Pak, S. Kim, D. Kim, E. Lee
Hanyang University, Korea
- P3042A **Optical and structural properties of ZnTe:O thin films deposited by radio frequence sputtering method**
S. Kim, S. Pak, E. Kim
Hanyang University, Korea

- P3043A **The effect of light exposure on the electrical properties of GeO₂/Ge gate stack**
K. Ndari, T. Wakana, S. Mitsuo, N. Osamu, Z. Shigeaki
Nagoya University, Japan
- P3044A **Deposition of high hardness metal coating by using microwave plasma spray**
A. Ahmad Mokhtar, T. Yasui, M. Fukumoto
Toyohashi University of Technology, Japan
- P3045A **Size effect of Hf nitridation under nitrogen plasma exposure**
T. Kitajima, T. Nakano
National Defense Academy, Japan
- P3046A **The improvement of all solid state electrochromic device with the post atmosphere pressure plasma treatment**
M. Wang, C. Yang, D. Jan, C. Ai
Institute of Nuclear Energy Research, Taiwan
- P3047A **2-D ablated plasma production process for pulsed ion beam-solid target**
¹T. Rungsrithana, ¹V. Rungsetthaphat, ²S. Azuma, ²N. Harada
¹University of the Thai Chamber of Commerce, Thailand
²Nagaoka University of Technology, Japan
- P3048A **Microstructures and optoelectronic properties of ITO films prepared by ion beam sputtering**
¹L. Gaik Teoh, ²J. Shen, ²S. Yeh
¹National Pingtung University of Science and Technology, Taiwan
²Metal Industries Research and Development Center, Taiwan
- P3049B **Enhancement of optical polarization anisotropy of a-plane InGaN/GaN mutiple quantum wells structure from violet to blue-green light**
¹S. Su, ^{1,2}Y. Su, ²S. Huang, ²H. Hsu, ¹C. Lin
¹National Cheng Kung University, Taiwan
²National Cheng Kung University, Taiwan
- P3050B **Molecular dynamics simulation of vapor phase growth process of GaN**
T. Miki, T. Kawamura, S. Kotake, Y. Suzuki
Mie University, Japan

- P3051B **Formation of GaN nanostructures on the apex of GaN pyramids by using of metal catalysts**
W. Yun, D. Jo, J. Ok, H. Jeon, G. Lee, S. Jung, S. Bae, H. Ahn, M. Yang
Korea Maritime University, Korea
- P3052B **Influence of AlN and LT-GaN buffer layer on the quality of GaN films grown on 6H-SiC substrate by MOCVD**
¹M. Chuang, ¹Y. Su, ¹S. Huang, ²J. Lin, ³Y. Hsu
¹National Cheng Kung University, Taiwan
²Chung Shan Institute of Science and Technology, Taiwan
³National Chiao Tung University, Taiwan
- P3053B **Growth of ZnO/GaN core/shell nanorods by plasma-enhanced chemical vapor deposition**
¹T. Wu, ¹L. Yi-chen, ^{1,2,3}H. Franklin Chau-nan
¹National Cheng-Kung University, Taiwan
²National Cheng-Kung University, Taiwan
³National Cheng-Kung University, Taiwan
- P3054B **Innovative thin films and nanostructures for thermal management of high power high frequency devices**
A. Abdou, Y. Scudeller
Institut Des matériaux Jean Rouxel, France
- P3055B **The influence of seed detachment on the growth of GaN nanowires**
W. Hou, T. Wu, W. Tang, W. Tsai, F. Hong
National Cheng Kung University, Taiwan
- P3056B **Patterning and void shape control of GaN-sapphire substrates**
¹S. Suihkonen, ¹O. Svensk, ¹S. Sintonen, ¹M. Sopanen, ¹H. Lipsanen, ²M. Ali, ²P. Torma
¹Aalto University, Finland
²OptoGaN GmbH, Germany
- P3057B **HRTEM analyses of GaN/AlInN/(111)Si grown by MOVPE**
¹S. Kawakita, ¹I. Hiroyuki, ¹S. Nobuhiko, ²I. Masashi, ²H. Yoshio, ²Y. Masahito, ²A. Hiroshi
¹Aichi Institute of Technology, Japan
²Nagoya University, Japan
- P3058B **Study on AlInN/GaN structures on AlN templates for ultraviolet photodiodes**
Y. Sakai, P. C. Khai, T. Egawa
Nagoya Institute of Technology, Japan

P3059B	Study of 365nm light-emitting diodes with various Al compositions in AlGaN quantum barrier
	¹ Y. Lu, ² Y. Fu, ² R. Xuan, ¹ Y. Su	
	¹ National Cheng Kung University, Taiwan	
	² Industrial Technology Research Institute, Taiwan	
P3060B	Electrical characteristics of surface stoichiometry controlled p-GaN Schottky contacts
	¹ K. Shiojima, ¹ T. Takahashi, ² N. Kaneda, ² T. Mishima, ³ T. Kajiwara, ³ S. Tanaka	
	¹ University of Fukui, Japan	
	² Hitachi Cable, Japan	
	³ Kyushu University, Japan	
P3061B	Effect of Carbon impurity incorporation on band-gap states in AlGaN/GaN hetero-structures
	¹ Y. Nakano, ² Y. Irokawa, ³ Y. Sumida, ³ S. Yagi, ³ H. Kawai	
	¹ Chubu University, Japan	
	² National Institute for Material Science, Japan	
	³ POWDEC, Japan	
P3062B	Optical study of the Sb surfactant effect on InGaAsN multiple quantum wells
	¹ H. Hsu, ² W. Chen, ² Y. Su	
	¹ Ming Chi University of Science and Technology, Taiwan	
	² National Cheng Kung University, Taiwan	
P3063B	Blue light-emitting diodes with a radiated-cone-shaped structure at GaN/sapphire interface
	C. Lin, S. Chen, T. Yu, C. Lin, B. Shieh, K. Chen, J. Dai	
	National Chung Hsing University, Taiwan	
P3064B	Size-dependent resonant-cavity light-emitting diodes for collimating concerns
	¹ Y. Chu, ¹ S. Yan-kuin, ² C. Chia-hsin, ² Y. Wen-yung	
	¹ National Cheng Kung University, Taiwan	
	² Industrial Technology Research Institute, Taiwan	
P3065B	Studies on the hydrophobic modification by plasma integrated with organic light-emitting polymer onto LED through spin coating and ink-jet printing
	¹ Y. Chu, ¹ S. Yan-kuin, ² C. Chia-hsin, ² Y. Wen-yung	
	¹ National Cheng Kung University, Taiwan	
	² Industrial Technology Research Institute, Taiwan	

- P3066B **A high efficiency InGaN solar cell with graded energy-gap top layer**
T. Fujisawa, N. Sawaki
Aichi Institute of Technology, Japan
- P3067B **Effect of Silicon doping in the AlGaN barrier on optoelectronic characteristics of ultraviolet light-emitting diodes**
¹Y. Lu, ²Y. Fu, ¹Y. Su, ¹H. Yu, ²R. Xuan
¹National Cheng Kung University, Taiwan
²Industrial Technology Research Institute, Taiwan
- P3068B **Effect of chemical wet-etching process of GaN substrate with a roughened backside on InGaN-based near-ultraviolet and blue light-emitting diodes**
¹Y. Lu, ²F. Yi-keng, ³C. Bo-chun, ²X. Rong, ²C. Chia-hsin, ¹S. Yan-kuin, ³H. Kai-feng
¹National Cheng Kung University, Taiwan
²Industrial Technology Research Institute, Taiwan
³National Chiao Tung University, Taiwan
- P3069B **Optimum temperature to grow nano-AlC on sapphire by metalorganic chemical vapor deposition**
S. Sakai, S. Wada
Tokushima University, Japan
- P3070B **Synthesis of GaN nanoneedles/organic hybrid heterostructure for light emitting diode.**
¹M. Shin, ¹M. Kim, ¹H. Ahn, ¹S. Yi, ²Y. Yu, ³N. Sawaki
¹Korea Maritime University, Korea
²Pukyong National University, Korea
³Aichi Institute of Technology, Japan
- P3071B **Fabrication of hybrid solar cell with vertically aligned GaN nanostructures and P₃HT conjugated polymer**
¹M. Kim, ¹M. Shin, ¹H. Ahn, ¹S. Yi, ²Y. Yu, ³N. Sawaki
¹Korea Maritime University, Korea
²Pukyong National University, Korea
³Aichi Institute of Technology, Japan

- P3072B **Characterization of GaN LED with Al, In contents grown by HVPE**
¹G. Lee, ¹H. Jeon, ¹S. Jung, ¹S. Bae, ¹K. Kim, ¹S. Yi, ¹M. Yang, ¹H. Ahn, ²Y. Yu, ³H. Ha, ⁴S. Hwan, ⁵N. Sawaki
¹Korea Maritime University, Korea
²Pukyung National University, Korea
³CSSOL. Co., Ltd., Korea
⁴Andong National University, Korea
⁵Aichi Institute of Technology, Korea
- P3073B **Application of barrierless metallization for fabricating making copper alloy film for fine interconnects**
C. Lin
Asia-Pacific Institute of Technology, Taiwan
- P3074B **Low dislocation densities on Nitride-based LEDs with a preflow of NH₃ source before growth of AlN buffer layer**
¹C. Wang, ¹Y. Chiou, ¹D. Sun, ²T. Chiang
¹Southern Taiwan University, Taiwan
²National Cheng Kung University, Taiwan
- P3075B **Reducing the current crowding effect on nitride-based LEDs using modulated P-extension electrode thickness**
¹Y. Chiou, ¹C. K. Wang, ¹D. J. Sun, ²T. H. Chiang
¹Southern Taiwan University, Taiwan
²National Cheng Kung University, Taiwan
- P3076B **Electrical characteristics of AlGaN/GaN HEMT with plasma induced damages**
T. Takimoto, K. Takeshita, S. Nakamura, T. Okumura
Tokyo Metropolitan University, Japan
- P3077B **Ultraviolet photodetectors using transparent gate AlGaN/GaN HEMT**
T. Narita, A. Wakejima, T. Egawa
Nagoya Institute of Technology, Japan
- P3078B **Consideration of the possibility of normally-off operation in GaN devices**
Y. Sakai, L. Selvaraj, O. Oda, T. Egawa
Nagoya Institute of Technology, Japan

- P3079C **Parameter-controlled growth of MWCNTs and carbon nanoribbons on carbon substrates via metal-catalyst-free chemical vapor deposition**
J. Lin, Z. Zeng, J. Lee
National University of Tainan, Taiwan
- P3080C **Epitaxial graphene on Si (111) substrate by pulse arc plasma deposition**
K. Banno, K. Fujita, H. Aryal, T. Egawa
Nagoya Institute of Technology, Japan
- P3081C **Graphene deposited on copper substrate by hot wire CVD**
V. F. Soler, B. Jordi, C. Carles, P. Esther, B. Enric, A. J. Luis
Universitat de Barcelona, Spain
- P3082C **Graphene sheets anchored with tin oxide nanoparticles as anode of Li-ion batteries**
J. Lin, L. Jia-yi, H. Chien-te
Yuan Ze University, Taiwan
- P3083C **Influence of oxidation levels on wetting properties of graphene sheets**
Y. Chen, C. Hsieh, B. Yang
Yuan Ze University, Taiwan
- P3084C **Characterization of iridium dioxide-carbon nanotube nanocomposites grown on graphene for electric double layer capacitor**
Y. Shih
National Taiwan University of Science and Technology, Taiwan
- P3085C **Formation of carbon nanowall on nanofiber by means of pulsed plasma CVD**
¹M. Matsushima, ²M. Noda, ¹H. Uchida, ¹M. Umeho, ¹K. Wakita
¹Chubu University, Japan
²Pulse Plasma Technology GK, Japan
- P3086C **Evaluation of crystallographic properties of carbon nanowalls by Raman spectroscopy**
¹H. Shimoeda, ¹H. Kondo, ¹K. Ishikawa, ²M. Hiramatsu, ¹M. Sekine, ¹M. Hori
¹Nagoya University, Japan
²Meijo University, Japan
- P3087C **Magnetic properties of carbon nanotubes filled with iron**
A. Nagata, H. Sato, S. Nakamura, T. Kaneko, Y. Fujiwara
Mie University, Japan

- P3088C **Formation and characteristics of TiO₂ nanoparticles-supported carbon nanowalls fabricated employing supercritical fluid**
¹T. Horibe, ²S. Mitsuguchi, ³H. Kano, ¹H. Kondo, ¹K. Ishikawa, ²M. Hiramatsu, ¹M. Sekine, ¹M. Hori
¹Nagoya University, Japan
²Meijo University, Japan
³NU Eco Engineering, Co., Ltd., Japan
- P3089C **Electrical properties and crystalline structures of carbon nanowalls grown by CH₄/H₂ plasma**
H. Cho, H. Kondo, K. Ishikawa, M. Sekine, M. Hori
Nagoya University, Japan
- P3090C **Formation of super-hydrophilic surface of CNWs employing atmospheric pressure plasma treatment**
¹H. Watanabe, ¹H. Kondo, ²M. Hiramatsu, ¹M. Sekine, ¹M. Hori
¹Nagoya University, Japan
²Meijo University, Japan
- P3091C **Surface-enhanced raman spectra of multiwalled carbon nanotube and carbon nanowire**
¹X. Zhao, ¹X. Hou, ¹L. Sheng, ²Y. Ando
¹Shanghai University, China
²Meijo University, Japan
- P3092C **Carbon and carbide nanomaterials synthesized by a pulsed plasma in liquid method**
¹Z. Abdullaeva, ²O. Emil, ³I. Chihiro, ²T. Shintaro, ⁴S. Saadat, ⁵M. Tsutomu
¹Kumamoto University, Japan
²Kumamoto University, Japan
³Kumamoto University, Japan
⁴Institute of Chemistry and Chemical Technology, Kyrgyz
⁵Kumamoto University, Japan
- P3093C **Formation of bamboo-like carbon nanotubes over copper catalysts**
S. Chen, J. Lin
National University of Tainan, Taiwan
- P3094C **A carbon nanotube sensor for ammonia monitoring with Au nanoparticle**
¹Z. Lin, ¹S. Young, ³C. Huang, ²C. Hsiao
¹Formosa University, Taiwan
²Cheng Kung University, Taiwan
³National Yunlin University of Science and Technology, Taiwan

- P3095C **Carbon-based solar cell from electrically conductive amorphous carbon deposited by self-prepared aerosol-assisted CVD (AACVD)**
N. Ahmad
Universiti Teknologi Mara (UiTM), Malaysia
- P3096C **Raman scattering in amorphous carbon and its opto-electrical characterizations**
N. Ahmad
Universiti Teknologi Mara (UiTM), Malaysia
- P3097C **ZnO/carbon nanotube branched nanorod for carbon dioxide monitoring sensor**
¹J. Guo, ¹C. Huang, ¹K. Chen, ²S. Young, ³C. Hsiao, ³C. Chang
¹National Yunlin University of Science and Technology, Taiwan
²National Formosa University, Taiwan
³National Cheng Kung University, Taiwan
- P3098C **Characteristics of graphene field-effect transistors on silicon(111) substrate**
H. Aryal, K. Fujita, T. Egawa
Nagoya Institute of Technology, Japan
- P3099C **Nucleation control of self-organized graphenes using inductively coupled plasma enhanced chemical vapor deposition**
¹Y. Nihashi, ¹M. Hiramatsu, ²H. Kondo, ²M. Hori
¹Meijo University, Japan
²Nagoya University, Japan
- P3100C **SEM observation of carbon nanomaterials using ionic liquids**
S. Abe, A. Hyono, T. Yonezawa
Hokkaido University, Japan
- P3102C **On the thin film of nanocrystalline graphite clusters**
N. Ray, J. Datta, H. Biswas
Saha Institute of Nuclear Physics, India
- P3103C **Fabrication of graphene-based films using microwave plasma-enhanced CVD**
¹M. Naito, ¹M. Hiramatsu, ²H. Kondo, ²M. Hori
¹Meijo University, Japan
²Nagoya University, Japan

P3104C	Optical emission spectroscopy of arc plasma for synthesizing carbon nanotubes
	¹ A. Ando, ¹ T. Suzuki, ¹ S. Inoue, ¹ T. Ohta, ¹ Y. Ando, ¹ M. Ito, ² M. Hori	
	¹ Meijo University, Japan	
	² Nagoya University, Japan	
P3105C	Synthesis of graphene and CNTs on Ni substrate with acetylene by CVD
	¹ M. Chuang, ¹ Y. Su, ² C. Huang, ² J. Tsai, ³ S. Young, ¹ C. Hsiao	
	¹ National Cheng Kung University, Taiwan	
	² National Yunlin University of Science and Technology, Taiwan	
	³ National Formosa University, Taiwan	
P3106C	Radical densities in microwave plasma-enhanced chemical vapor deposition employing carbon-containing gas mixture
	¹ K. Murata, ¹ M. Hiramatsu, ² S. Takashima, ³ H. Kondo, ³ M. Hori	
	¹ Meijo University, Japan	
	² Plasma Center for Industrial Applications, Japan	
	³ Nagoya University, Japan	
P3107C	Fabrication of carbon nanowalls on carbon fiber paper for fuel cell application
	¹ S. Mitsuguchi, ¹ M. Hiramatsu, ² H. Kondo, ² M. Hori	
	¹ Meijo University, Japan	
	² Nagoya University, Japan	
P3108C	Electron field emission properties of carbon nanostructures
	¹ T. Horaguchi, ¹ M. Hiramatsu, ² M. Hori, ² H. Kondo	
	¹ Meijo University, Japan	
	² Nagoya University, Japan	
P3109C	Nano-carbon electrode having large capacitance prepared by pulsed plasma CVD using Ni catalysis
	¹ K. Kato, ¹ M. Matsushima, ¹ Y. Matsuura, ² M. Noda, ¹ M. Umeno, ¹ H. Utida	
	¹ Chubu University, Japan	
	² Pulse Plasma Technology GK, Japan	
P3110C	Effect of catalyst film thickness on growth of carbon nanotubes by low pressure alcohol catalytic chemical vapor deposition
	D. Sawaguchi, M. Takaya, S. Hideki, M. Hideto, H. Kazumasa	
	Mie University, Japan	

- P3111C **Preparation of graphite polyhedral particle by transferred arc under atmospheric pressure**
F. Liang, S. Tasuku, T. Manabu, C. Sooseok, W. Takayuki
Tokyo institute of technology, Japan
- P3112C **Carbon nanotube on porous silicon support: a diameter controlled synthesis**
¹N. Asli, ²S. Abu Bakar, ¹S. Mohamad Yusop, ¹M. Mahmood, ¹S. Abdullah
¹Universiti Teknologi MARA, Malaysia
²Universiti Pendidikan Sultan Idris, Malaysia
- P3113C **Heterojunction solar cell**
¹S. Adhikari, ¹M.S. Kayastha, ¹D.C. Ghimire, ²T. Takeuchi, ²K. Murakami, ²Y. Kawashimo, ¹H. Uchida, ¹K. Wakita, ¹M. Umeno
¹Chubu University, Japan
²Shinko Seiki Co., Ltd., Japan
- P3114C **DFT study on interaction of radicals and atoms with graphene surface**
H. Tachikawa, H. Kawabata
Hokkaido University, Japan
- P3115C **Effects of deposition time on growth of carbon nano-fibers by DC-plasma CVD**
D. Ghimire
Chubu University, Japan
- P3116C **Synthesis of carbon fiber-nanoube hybrid and its application in polymer composites**
¹M. Kumar, ²H. Takeshi, ³Y. Tomohiro, ¹A. Yoshinori
¹Meijo University, Japan
²Meijo Nano Carbon Co., Ltd., Japan
³Aichi Industrial Technology Institute, Japan
- P3117C **Electrical properties of B-doped ultrananocrystalline diamond**
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